

ABSTRACT

"Method of Feeding Gas into Chamber"

A method of feeding into a chamber (3) to form a film on a wafer, alternately reaction gas through a reactive gas feed line (1) comprising a chamber pressure regulator 4 and a line changeover valve (V_1), and inert gas through an inert gas feed line (2) comprising a chamber pressure regulator 5 and a line changeover valve (V_2), wherein shunt valves (V_3, V_4), are connected to the primary side of the changeover valves V_1, V_2 of the lines 1, 2 and a vent line 6 is connected to the outlet side of the shunt valves V_3, V_4 , the line changeover valve V_1 of the reactive gas feed line 1 and shunt valve V_4 of inert gas feed line 2 being opened and closed together and the line changeover valve V_2 of the inert gas feed line 2 and the shunt valve V_3 of the reactive gas feed line 1 being opened and closed together at specific time intervals while the vent line 6 is evacuated, so that the reactive gas and inert gas may be alternately fed into the chamber 3 from the reactive gas feed line 1 and inert gas feed line 2.

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(Please note that Figure 1 should accompany the abstract when published)